Andrea PajdarovÃ¡

List of Publications by Year
in descending order

29 papers	934 citations	567281 15 h-index	501196 28 g-index
29 all docs	29 docs citations	29 times ranked	761 citing authors

#	Article	IF	Citations
1	On density distribution of Ti atom and ion ground states near the target in HiPIMS discharge using cavity ring-down spectroscopy and laser induced fluorescence. Plasma Sources Science and Technology, 2022, 31, 05LT04.	3.1	3
2	Dependence of characteristics of Hf(M)SiBCN (MÂ=ÂY, Ho, Ta, Mo) thin films on the M choice: Ab-initio and experimental study. Acta Materialia, 2021, 206, 116628.	7.9	7
3	High-performance thermochromic VO2-based coatings with a low transition temperature deposited on glass by a scalable technique. Scientific Reports, 2020, 10, 11107.	3.3	29
4	Microstructure of High Temperature Oxidation Resistant Hf6B10Si31C2N50 and Hf7B10Si32C2N44 Films. Coatings, 2020, 10, 1170.	2.6	2
5	Pulsed Magnetron Sputtering of Strongly Thermochromic VO2-Based Coatings with a Transition Temperature of 22 Â°C onto Ultrathin Flexible Glass. Coatings, 2020, 10, 1258.	2.6	11
6	Ion energy distributions at substrate in bipolar HiPIMS: effect of positive pulse delay, length and amplitude. Plasma Sources Science and Technology, 2020, 29, 065003.	3.1	22
7	Plasma parameters in positive voltage pulses of bipolar HiPIMS discharge determined by Langmuir probe with a sub-microsecond time resolution. Plasma Sources Science and Technology, 2020, 29, 085016.	3.1	18
8	Effect of energetic particles on pulsed magnetron sputtering of hard nanocrystalline MBCN (Mâ€¯=â€¯Ti, Zr,) Tj ETQq0 0 0 rgBT /Overloc	1.8	7
9	High-rate reactive high-power impulse magnetron sputtering of transparent conductive Al-doped ZnO thin films prepared at ambient temperature. Thin Solid Films, 2019, 679, 35-41.	1.8	12
10	Effects of power per pulse on reactive HiPIMS deposition of ZrO2 films: A time-resolved optical emission spectroscopy study. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, 061305.	2.1	0
11	Ion-flux characteristics during low-temperature (300 Â°C) deposition of thermochromic VO₂ films using controlled reactive HiPIMS. Journal Physics D: Applied Physics, 2019, 52, 025205.	2.8	10
12	Optical emission spectroscopy during the deposition of zirconium dioxide films by controlled reactive high-power impulse magnetron sputtering. Journal of Applied Physics, 2017, 121, .	2.5	14
13	Reactive high-power impulse magnetron sputtering of ZrO2 films with gradient ZrOx interlayers on pretreated steel substrates. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 031503.	2.1	7
14	Dynamics of processes during the deposition of ZrO2 films by controlled reactive high-power impulse magnetron sputtering: A modelling study. Journal of Applied Physics, 2017, 122, 043304.	2.5	8
15	Microstructure of hard and optically transparent HfO2 films prepared by high-power impulse magnetron sputtering with a pulsed oxygen flow control. Thin Solid Films, 2016, 619, 239-249.	1.8	25
16	Absolute OH and O radical densities in effluent of a He/H₂O micro-scaled atmospheric pressure plasma jet. Plasma Sources Science and Technology, 2016, 25, 045013.	3.1	46
17	A parametric model for reactive high-power impulse magnetron sputtering of films. Journal Physics D: Applied Physics, 2016, 49, 055202.	2.8	34
18	Hard multifunctional Hfâ€"Bâ€"Siâ€"C films prepared by pulsed magnetron sputtering. Surface and Coatings Technology, 2014, 257, 301-307.	4.8	20

#	Article	IF	Citations
19	Effect of Nitrogen Content on the Microstructure and Hardness of Hard Zrâ€“Bâ€“Câ€“N Films. Microscopy and Microanalysis, 2014, 20, 1892-1893.	0.4	2
20	Transport and ionization of sputtered atoms in high-power impulse magnetron sputtering discharges. Journal Physics D: Applied Physics, 2013, 46, 105203.	2.8	19
21	Effect of voltage pulse characteristics on high-power impulse magnetron sputtering of copper. Plasma Sources Science and Technology, 2013, 22, 015009.	3.1	6
22	A non-stationary model for high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2011, 110, .	2.5	33
23	Ion Flux Characteristics in Pulsed Dual Magnetron Discharges Used for Deposition of Photoactive TiO₂ Films. Plasma Processes and Polymers, 2011, 8, 191-199.	3.0	10
24	Electron energy distributions and plasma parameters in high-power pulsed magnetron sputtering discharges. Plasma Sources Science and Technology, 2009, 18, 025008.	3.1	76
25	High-power pulsed sputtering using a magnetron with enhanced plasma confinement. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 42-47.	2.1	75
26	Pulsed dc Magnetron Discharges and their Utilization in Plasma Surface Engineering. Contributions To Plasma Physics, 2004, 44, 426-436.	1.1	110
27	Reactive magnetron sputtering of Siâ€“Câ€“N films with controlled mechanical and optical properties. Diamond and Related Materials, 2003, 12, 1287-1294.	3.9	34
28	Pulsed dc magnetron discharge for high-rate sputtering of thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2001, 19, 420-424.	2.1	71
29	Collisional-radiative model for an argon glow discharge. Journal of Applied Physics, 1998, 84, 121-136.	2.5	223